

# Notice of Allowability

Application No.

10/665,995

Examiner

Anabel M. Ton

Applicant(s)

YU ET AL.

Art Unit

2875

## -- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to 09/26/06.
2. ☒ The allowed claim(s) is/are 11-22.
3. ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
  - a) ☒ All b) ☐ Some\* c) ☐ None of the:
    1. ☒ Certified copies of the priority documents have been received.
    2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
    3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

\* Certified copies not received: \_\_\_\_\_.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  
**THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.**

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
  5. ☐ CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
    - (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
      - 1) ☐ hereto or 2) ☐ to Paper No./Mail Date \_\_\_\_\_.
    - (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date \_\_\_\_\_.
- Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

### Attachment(s)

1. ☐ Notice of References Cited (PTO-892)
2. ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. ☐ Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date \_\_\_\_\_
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material
5. ☐ Notice of Informal Patent Application
6. ☐ Interview Summary (PTO-413), Paper No./Mail Date \_\_\_\_\_
7. ☐ Examiner's Amendment/Comment
8. ☒ Examiner's Statement of Reasons for Allowance
9. ☐ Other \_\_\_\_\_

## DETAILED ACTION

### *Allowable Subject Matter*

1. Claims 11-22 are allowed.
2. The following is an examiner's statement of reasons for allowance: The prior art cited does not anticipate individually nor teach in combination the following limitations in particular the feature of the arrangement of the light guide plate, diffusion plate, and reflection polarizer as recited in claims 11-13 and in particular the feature of the light conversion elements being configured on an outside surface of the diffusion plate, said outside surface of the diffusion plate facing towards the reflection polarizer and being opposite to the portion of diffusion plate positioned above the light guide plate.
  - A backlight system, comprising: a light guide plate; at least a light source; a diffusion plate located above said light guide plate; and a reflection polarizer which allows S polarized light to pass while reflecting P polarized light, the reflection polarizer being located above the diffusion plate; wherein the light guide plate, the diffusion plate and the reflection polarizer are stacked one on another in sequence, and a plurality of light conversion elements are configured at an outside of the diffusion plate to transform the reflected P polarized light thereabouts to a common light and successively redirect the common light toward the reflection polarizer without substantial involvement of the diffusion plate and the light guide plate outside of the diffusion plate facing toward the reflection polarizer and being opposite to the portion of diffusion plate stacked on the light guide plate.

- A method of making a backlight system, comprising steps of: providing a light guide plate; positioning a light source beside said light guide plate; positioning a diffusion plate above said light guide plate; positioning a reflection polarizer above said diffusion plate which allows S polarized lights light to pass and reflects P polarized lights light; and forming a plurality of light conversion elements on an outside surface of said diffusion plate, so as to transform the reflected P polarized light to a common light thereabouts and successively redirect the common light toward the reflection polarizer without substantial involvement of at least said light guide plate, outside surface of the diffusion plate facing toward the reflection polarizer and being opposite to the portion of diffusion plate positioned above the light guide plate.
- A backlight system, comprising: a light guide plate; a diffusion plate located above said light guide plate; and a reflection polarizer which allows light polarized in one certain direction to pass while reflecting light perpendicular to the certain direction, the located above the diffusion plate; wherein polarized in a direction reflection polarizer being the light guide plate, the diffusion plate and the reflection polarizer are stacked one on another in sequence, and a plurality of light conversion elements are configured at an outside surface of the diffusion plate, said outside surface of the diffusion plate facing toward the reflection polarizer and being opposite to the portion of diffusion plate stacked on the light guide plate.

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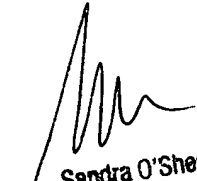
Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Anabel M. Ton whose telephone number is (571) 272-2382. The examiner can normally be reached on 08:00-16:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Sandra O'Shea can be reached on (571) 272-2378. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Anabel M Ton  
Examiner  
Art Unit 2875



Sandra O'Shea  
Supervisory Patent Examiner  
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AMT

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